

Supporting Information

Local Temperature Reduction Induced Crystallization of MASnI_3 and Achieving a Direct Wafer Production

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Fig. S1. Photo pictures of the wafers fetched from the bottom of the precursor solution.



Fig. S2. Cool water drop induced crystallization and wafer production of MASnI₃

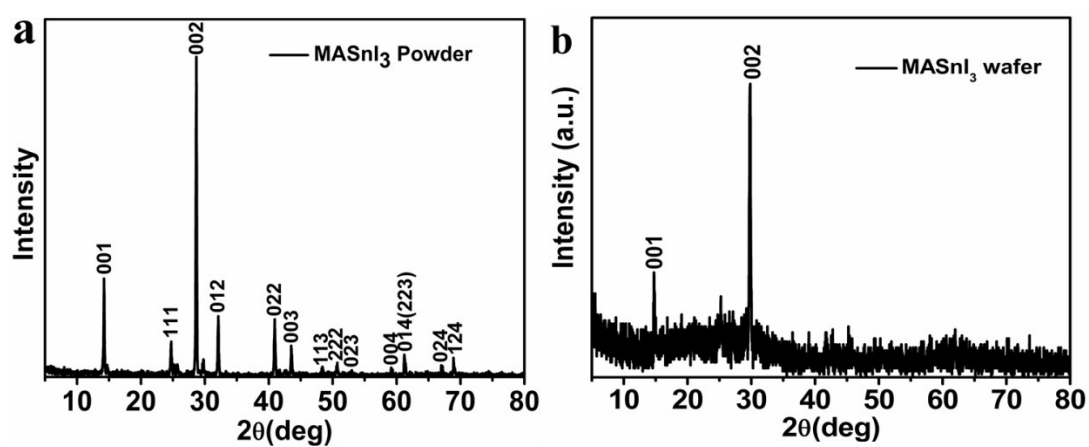


Fig. S3. X-ray diffraction patterns of MASnI₃ powder and MASnI₃ wafer obtained by cool water drop induced crystallization of MASnI₃.



Fig. S4. Diethyl ether anhydrous drop induced crystallization of MASnI_3 wafer.

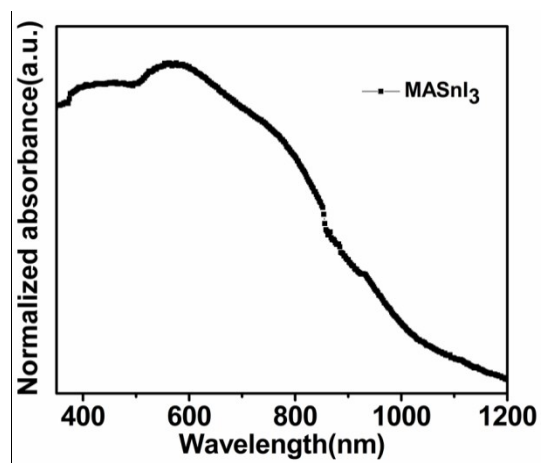


Fig. S5. UV-vis-NIR absorption spectrum of MASnI_3 wafer fabricated by cool water drop induced crystallization.